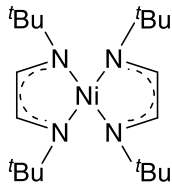


Catalog # 28-0225 Bis(1,4-di-t-butyl-1,3-diazabutadienyl)nickel(II) Ni(DAD)₂, min. 98% (99.999%-Ni)
PURATREM



Thermal Behavior:

- Sublimation: 115°C/0.05 Torr [1]
- Melting point: 184-185°C [1]
- Decomposition: 230°C [1]
- TGA diagram and data is available [1]

Technical Notes:

1. ALD/CVD precursor for nickel containing thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Ni	ALD	100-160°C	1 Torr	O ₃	185-200°C	2

References:

1. [Organometallics 2011, 30, 5010.](#)
2. U.S. 2016, US 9255327 B2 20160209 .
3. [Chem. Mater., 2017, 29, 7458-7466.](#)
4. [ACS Appl. Mater. Interfaces 2019, 11, 30437.](#)